

Refine Search

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Terms	Documents
aluminum adj nitrate and copper and dielectric and (tantalum adj nitride or tantalum or ta or tan) and first adj5 (cmp or polishing or planarizing) adj3 (slurry or step) and second adj5 (cmp or polishing or planarizing) adj3 (slurry or step)	0

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Search History

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DB=PGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ

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|--|--------------|
| <u>L19</u> aluminum adj nitrate and copper and dielectric and (tantalum adj nitride or tantalum or ta or tan) and first adj5 (cmp or polishing or planarizing) adj3 (slurry or step) and second adj5 (cmp or polishing or planarizing) adj3 (slurry or step) | 0 <u>L19</u> |
| <u>L18</u> ammonium adj nitrate and copper and dielectric and (tantalum adj nitride or tantalum or ta or tan) and first adj5 (cmp or polishing or planarizing) adj3 (slurry or step) and second adj5 (cmp or polishing or planarizing) adj3 (slurry or step) | 6 <u>L18</u> |
| <u>L17</u> (hydroxylamine adj nitrate or hydrazine) and copper and dielectric and (tantalum adj nitride or tantalum or ta or tan) and first adj5 (cmp or polishing or planarizing) adj3 (slurry or step) and second adj5 (cmp or polishing or planarizing) adj3 (slurry or step) | 0 <u>L17</u> |

DB=PGPB,USPT; PLUR=YES; OP=ADJ

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|---|--------------|
| <u>L16</u> L14 and (polish or polishing) adj stop | 0 <u>L16</u> |
|---|--------------|

<u>L15</u>	L14 and (phase adj one or first or initially or initial) adj3 (cmp or chemical adj mechanical adj (polishing or polish or planarization)) adj2 (slurry or step or composition)	1	<u>L15</u>
<u>L14</u>	L13 and (hydroxylamine or hydroxyl adj amine or ammonium adj nitrate or aluminum adj nitrate or hydrazine)	14	<u>L14</u>
<u>L13</u>	L10 or L11 or L12	38	<u>L13</u>
<u>L12</u>	20020062600 or 20010037821	2	<u>L12</u>
<u>L11</u>	US-6149696-\$.DID. OR US-6299795-\$.DID. OR US-6117775-\$.DID. OR US-6461227-\$.DID. US-6156661-\$.DID. OR US-6140239-\$.DID. OR US-6117733-\$.DID. OR US-6063306-\$.DID. OR US-5954997-\$.DID. OR US-5981454-\$.DID. OR US-5899740-\$.DID. OR US-5897375-\$.DID. OR US-5863307-\$.DID. OR US-5858813-\$.DID. OR US-5840629-\$.DID. OR US-5780358-\$.DID. OR US-5770517-\$.DID. OR US-5735963-\$.DID. OR US-5614444-\$.DID. OR US-5575837-\$.DID. OR US-5527423-\$.DID. OR US-5354490-\$.DID. OR US-5340370-\$.DID. OR US-5225034-\$.DID. OR US-4724042-\$.DID. OR US-4556449-\$.DID. OR US-4013758-\$.DID. OR US-3592773-\$.DID. OR US-3410802-\$.DID. OR US-3385682-\$.DID. OR US-3137600-\$.DID. OR US-6293848-\$.DID. OR US-6398827-\$.DID. OR US-4959113-\$.DID. OR US-4204013-\$.DID. OR US-5281311-\$.DID.	4	<u>L11</u>

DB=PGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ

<u>L8</u>	L8 and (phase adj one or first or initially or initial) adj3 (cmp or chemical adj mechanical adj (polishing or polish or planarization)) adj2 (slurry or step or composition)	4	<u>L9</u>
<u>L8</u>	abrasive and aluminum adj nitrate and copper and (dielectric or insulating) and (tantalum or tantalum adj nitride)	49	<u>L8</u>
<u>L7</u>	abrasive and aluminum adj nitrate and copper and (dielectric or insulating) and (tantalum or tantalum adj nitride) and (polishing or polish)adj stop	0	<u>L7</u>
<u>L6</u>	abrasive and (ammonium or aluminum) adj4 nitrate and copper and dielectric and (tantalum or tantalum adj nitride) and (phase adj one or first or initially or initial) adj3 (cmp or chemical adj mechanical adj (polishing or polish or planarization)) adj2 (slurry or step or composition)	34	<u>L6</u>
<u>L5</u>	L3 and (phase adj one or first or initially or initial) adj3 (cmp or chemical adj mechanical adj (polishing or polish or planarization)) adj2 (slurry or step or composition)	3	<u>L5</u>
<u>L4</u>	L1 and (phase adj one or first or initially or initial) adj3 (cmp or chemical adj mechanical adj (polishing or polish or planarization)) adj2 (slurry or step or composition)	13	<u>L4</u>
<u>L3</u>	L2 and (cmp or chemical adj mechanical adj (polish or polishing))	33	<u>L3</u>
<u>L2</u>	hydrazine and copper and dielectric and (tantalum or tantalum adj nitride) and (nitrate or nitric adj acid)	85	<u>L2</u>
<u>L1</u>	(hydroxylamine or hydroxyl adj amine) near4 nitrate and copper and dielectric and (tantalum or tantalum adj nitride) and (nitrate or nitric adj acid)	24	<u>L1</u>

END OF SEARCH HISTORY